



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Re Application of:  
Ratnam SOORIYAKUMARAN et al.

Confirmation No.: 7983

Serial No.: 10/079,289

Group Art Unit: 1752

Filing Date: February 19, 2002

Examiner: Yvette C. THORNTON

Title: FLUORINATED SILSESQUIOXANE POLYMERS  
AND USE THEREOF IN LITHOGRAPHIC  
PHOTORESIST COMPOSITIONS (as amended  
herein)

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OCT 31 2003  
TC 1700

**THIRD PRELIMINARY AMENDMENT AND**  
**RESPONSE TO REQUIREMENT FOR RESTRICTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is in response to the Office Action mailed September 23, 2003 concerning the patent application referenced above. The Action sets forth a requirement for restriction and is not an Action on the merits. As such, a one-month shortened statutory period has been set for response. Applicants' response is set forth herein, along with amendments to the claims.

A Supplemental Information Disclosure Statement is submitted herewith, along with copies of the cited references, U.S. Patent Nos. 6,531,260 to Iwasawa et al. and 6,623,909 to Hatakeyama et al.

**An Amendment to the Title** is set forth on page 2 of this document.

**Amendments to the Claims** are reflected in the listing of the claims which begins on page 3 of this document.

**Remarks** begin on page 14 of this document.

**AMENDMENT TO THE TITLE**

On page 1 of the application, at lines 1-2, on page 71 of the application, at lines 1-2, and wherever the title appears in the application documents, please change the title to read

**-FLUORINATED SILSESQUIOXANE POLYMERS AND**  
**USE THEREOF IN LITHOGRAPHIC PHOTORESIST COMPOSITIONS--.**